

Stabilization of Low Valent Silicon Fluorides in the Coordination Sphere of Transition Metals

Ramachandran Azhakar, Rajendra S. Ghadwal,* Herbert W. Roesky,* Hilke Wolf, and Dietmar Stalke*

Institut für Anorganische Chemie der Universität Göttingen, Tammannstrasse 4, 37077 Göttingen, Germany

Supporting Information

ABSTRACT: Silicon(II) fluoride is unstable; therefore, isolation of the stable species is highly challenging and was not successful during the last 45 years. SiF₂ is generally generated in the gas phase at very high temperatures (~1100–1200 °C) and low pressures and readily disproportionates or polymerizes. We accomplished the syntheses of stable silicon(II) fluoride species by coordination of silicon(II) to transition metal carbonyls. Silicon(II) fluoride compounds L(F)Si·M(CO)₅ {M = Cr (4), Mo (5), W(6)} (L = PhC(NtBu)₂) were prepared by metathesis reaction from the corresponding chloride with Me₃SnF. However, the chloride derivatives L(Cl)Si·M(CO)₅ {M = Cr (1), Mo (2), W(3)} (L = PhC(NtBu)₂) were prepared by the treatment of transition metal carbonyls with L(Cl)Si.



Direct fluorination of L(Cl)Si with Me₃SnF resulted in oxidative addition products. Compounds 4-6 are stable at ambient temperature under an inert atmosphere of nitrogen. Compounds 4-6 were characterized by NMR spectroscopy, EI-MS spectrometry, and elemental analysis. The molecular structures of 4 and 6 were unambiguously established by single-crystal X-ray diffraction. Compounds 4 and 6 are the first structurally characterized fluorides, after the discovery of SiF₂ about four and a half decades ago.

■ INTRODUCTION

Taming of highly reactive species to be isolable at normal laboratory conditions is a challenging task in synthetic chemistry.¹ Carbenes and silylenes R_2E : (where $R = alkyl_1$, aryl, H, or halogen and E = C or Si) are highly reactive and play a constantly growing important role in synthetic organic and organosilicon chemistry as well as in material sciences.²⁻ Stable analogues of carbenes and silylenes have been isolated as N-heterocyclic carbenes (NHCs)⁵ and N-heterocyclic silylenes (NHSis).⁶ The reactivity of NHSis is comparable with that of the NHCs. The latter find many applications in chemistry.^{7,8} Gaseous dihalosilylenes $X_2Si: (X = F \text{ or } Cl)^{9,10}$ have been known for many years. However, they are not stable at room temperature; they condense to polymeric $(X_2Si)_n$ or disproportionate to $(SiX)_r$ and perhalosilanes. The properties and reactivity of gaseous X_2Si : and polymeric $(X_2Si)_r$ have been studied, but no stable analogue of halosilylene was known.¹¹ In 2006,^{6e} we reported on a base-stabilized monochlorosilylene L(Cl)Si (L = PhC(NtBu)₂), and later developed a facile method to access L(Cl)Si in almost quantitative yield using $LiN(SiMe_3)_2$ as a reducing agent.^{6f} Moreover, we isolated NHC stabilized dichlorosilylene NHC•Cl₂Si (NHC= 1,3-bis-(2,6diisopropylphenyl)imidazol-2-ylidene or 1,3-bis-(2,4,6trimethylphenyl)imidazol-2-ylidene) in high yield without using hazardous reducing agents such as alkali metals or KC₈. NHC·Cl₂Si was obtained by a new synthetic procedure comprising the reductive elimination of HCl from trichlorosilane in the presence of NHC under mild reaction conditions.¹² After the report of the chloro-derivatives, we focused our attention on the synthesis of stable silicon(II) fluoride. Due to the high propensity of fluorosilylene toward polymerization or disproportionation, attempts to isolate fluoro-analogues of LSiF

were not successful. However, we succeeded in the synthesis of $L(F)Si \cdot BH_3$ and $L(H)Si \cdot BH_3$ in which each silvlene base forms an adduct with the Lewis acid BH₃. L(F)Si·BH₃ was only characterized by NMR and mass spectrometry.¹³ Silylene has a stereoactive lone pair of electrons, which acts as a σ -donor ligand and forms complexes with transition metals by ligand substitution reactions.^{14,15} We have reported the properties of silvlenes as σ -donor ligands for the synthesis of transition metal complexes,¹⁵ as well as on its oxidative addition reactions with organic substrates¹⁶ and Lewis bases.¹⁷ Stabilization of highly reactive species in the coordination sphere of transition metals is of current interest;¹⁸ however, no fluorosilylene coordinate with a transition metal has been isolated so far. Herein, we report the stable silicon(II) fluoride species {L(F)Si·M(CO)₅, M = Cr (4), Mo (5), W(6)} (L = PhC(NtBu)₂), where 4 and 6 are the first structurally characterized silicon(II) fluoride derivatives.

RESULTS AND DISCUSSION

For the preparation of compounds **4–6** {L(F)Si·M(CO)₅, M = Cr (4), Mo (5), W(6)}, we assembled first the chloride derivatives **1–3** {L(Cl)Si·M(CO)₅ {M = Cr (1), Mo (2), W(3)} and treated these in 1:1 ratio with Me₃SnF as a fluorinating agent.¹⁹

Compounds 1–3 {L(Cl)Si·M(CO)₅, M = Cr (1), Mo (2), W(3)} were obtained in good yield in one pot reactions of L(Cl)Si with the respective $M(CO)_5(THF)$ in 1:1 ratio (Scheme 1). All compounds are soluble in benzene, toluene, and THF and insoluble in hexane and pentane. They are stable both in solution and solid state for a long period of time without any decomposition under an inert gas atmosphere. Compounds 1–3 were fully characterized by

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parameter	1•toluene	2	3•toluene	4	6
empirical formula	C27H31ClCrN2O5Si	C ₂₀ H ₂₃ ClMoN ₂ O ₅ Si	C27H31ClN2O5SiW	C ₂₀ H ₂₃ CrFN ₂ O ₅ Si	C ₂₀ H ₂₃ FN ₂ O ₅ SiW
fw	579.08	530.88	710.93	470.49	602.34
cryst syst	monoclinic	orthorhombic	triclinic	monoclinic	triclinic
space group	$P2_1/m$	P212121	$P\overline{1}$	$P2_{1}/n$	$P\overline{1}$
unit cell	a = 9.896(3) Å	a = 9.791(2) Å	a = 9.873(2) Å	a = 10.538(2) Å	a = 9.203(3)Å
dimensions	b = 13.060(5) Å	b = 13.307(2) Å	b = 11.621(3) Å	b = 18.0290(10) Å	b = 10.2800(10) Å
	c = 11.577(4) Å	c = 18.432(2) Å	c = 13.1260(10) Å	c = 12.411(3) Å	c = 13.187(2) Å
	$\beta = 98.60(2)^{\circ}$		$\alpha = 94.910(10)^{\circ}$	$\beta = 109.130(2)^{\circ}$	$\alpha=110.720(10)^\circ$
			$\beta = 93.04(2)^{\circ}$		$\beta = 99.33(2)^{\circ}$
			$\gamma=97.560(10)^\circ$		$\gamma=91.24(4)^\circ$
volume, Z	1479.4(9) Å ³ , 2	2401.5(7) Å ³ , 4	1484.4(5) Å ³ , 2	2227.7(7) Å ³ , 4	1147.2(4) Å ³ , 2
density (calcd)	1.300 g/cm ³	1.468 g/cm ³	1.591 g/cm ³	1.403 g/cm ³	1.744 g/cm ³
abs coeff	0.292 mm^{-1}	2.044 mm^{-1}	2.187 mm^{-1}	0.322 mm^{-1}	2.765 mm ⁻¹
F(000)	604	1080	704	976	588
crystal size/mm ³	$0.30\times0.21\times0.13$	$0.20\times0.20\times0.15$	$0.18\times0.16\times0.10$	$0.20 \times 0.15 \times 0.12$	$0.20\times0.20\times0.15$
θ range for data collection	1.40-20.28°	1.74–20.09°	1.23–20.81°	1.63–21.35°	1.32–20.91°
limiting indices	$\begin{array}{l} -12 \leq h \leq 12; -16 \leq k \\ \leq 14; -14 \leq l \leq 10 \end{array}$	$-11 \le h \le 11; -16 \le k \le 16; -22 \le l \le 22$	$\begin{array}{l} -12 \leq h \leq 12; -14 \leq k \\ \leq 14; 0 \leq l \leq 16 \end{array}$	$\begin{array}{l} -12 \leq h \leq 13; -23 \leq k \\ \leq 23; -16 \leq l \leq 16 \end{array}$	$\begin{array}{l} -11 \leq h \leq 11; -13 \leq k \\ \leq 13; -16 \leq l \leq 16 \end{array}$
reflns collected	13 702	17 349	62 539	36 069	68 180
indep reflns	$3068 \ (R_{\rm int} = 0.0229)$	4609 ($R_{\rm int} = 0.1123$)	6280 ($R_{\rm int} = 0.0303$)	$5057 \ (R_{\rm int} = 0.0285)$	4949 ($R_{\rm int} = 0.0419$)
completeness to θ	99.9% ($\theta = 20.28^{\circ}$)	99.8% ($\theta = 20.09^{\circ}$)	99.2% ($\theta = 20.81^{\circ}$)	99.1% ($\theta = 21.35^{\circ}$)	99.6% ($\theta = 20.91^{\circ}$
refinement method	full-matrix least-squares on F ²	full-matrix least-squares on F^2	full-matrix least-squares on F^2	full-matrix least-squares on F ²	full-matrix least-squares on F ²
data/restraints/ params	3068/363/284	4609/0/278	6280/111/353	5057/0/277	4949/0/277
GOFon F ²	1.062	1.042	1.087	1.039	1.065
final R indices $[I > 2\sigma(I)]$	R1 = 0.0313, wR2 = 0.0877	R1 = 0.0472, wR2 = 0.1175	R1 = 0.0205, wR2 = 0.0509	R1 = 0.0253, wR2 = 0.0670	R1 = 0.0139, wR2 = 0.0341
R indices (all data)	$\begin{array}{l} R1 = 0.0372, \\ wR2 = 0.0917 \end{array}$	R1 = 0.0558, wR2 = 0.1208	R1 = 0.0211, wR2 = 0.0514	R1 = 0.0287, wR2 = 0.0684	R1 = 0.0154, wR2 = 0.0352
largest diff peak and hole	0.306 and –0.363 e $\rm \AA^{-3}$	1.001 and $-1.021 \text{ e} \text{ Å}^{-3}$	1.965 and $-1.182 \text{ e} \text{ Å}^{-3}$	0.352 and –0.370 e $\rm \AA^{-3}$	1.098 and –0.861 e $\rm \AA^{-3}$

NMR spectroscopy, EI-MS spectrometry, elemental analysis, and single crystal X-ray structural analysis (Table 1).

The ¹H and ¹³C NMR spectra of 1–3 show usual resonances expected for the amidinate (L) and carbonyl groups. The ²⁹Si NMR spectra of 1–3 exhibit a single resonance each at δ 92.34, 72.75, and 52.99, which is shifted downfield when compared to L(Cl)Si (δ 14.6).^{6e} In compounds 1–3, the silicon atom is deshielded upon coordination to the metal atom. The chemical shifts are pertinent to the reported value of δ 62.69 for L(Cl)Si Ni(CO)₃.^{15d} Moreover 1–3 show their molecular ions in their mass spectra at *m*/*z* 486, 532, and 618, respectively.

The molecular structure of 1 is shown in Figure 1 (for 2 and 3, see Supporting Information). The selected bond parameters for compounds 1-3 are given in Table 2. The silicon atom is tetracoordinate and features distorted tetrahedral geometry comprising two nitrogen atoms from the supporting amidinato ligand, one chlorine atom, and one metal atom. The metal atom is hexacoordinate with a distorted octahedral geometry derived

from one silicon and five carbon atoms of the carbonyl groups. The Si-M bond distances in 1-3 are 2.3458(7), 2.4550(14), and 2.5086(11) Å. The average metal carbonyl bond lengths are 1.884(2), 1.998(6), and 2.038(4) Å, respectively. The Si-Cl bond length each in 1-3 is 2.1006(9), 2.1182(19), and 2.1012(14) Å [Si-Cl of L(Cl)Si, 2.156(1) Å]. The bite angle (N-Si-N) for 1-3 is 71.62(8)°, 71.34(18)°, and 71.41(12)°, respectively [N-Si-N of L(Cl)Si, 71.15(7)°].

Like 1-3, the respective fluorine derivatives 4-6 are soluble in benzene, toluene, and THF and insoluble in hexane and pentane. Furthermore, they are stable both in solution and the solid state for a long period of time without any decomposition provided they are stored in an inert gas atmosphere. Compounds 4-6 were characterized by NMR spectroscopy, EI-MS spectrometry, and elemental analysis. The molecular structures of 4 and 6 were unequivocally established by single crystal X-ray diffraction studies (Table 1).



Figure 1. Molecular structure of 1. Anisotropic displacement parameters are depicted at the 50% probability level.

Formation of the silicon(II) fluorides 4-6 was readily observed in their related ¹⁹F NMR spectrum. Compounds 4-6 exhibit a single ¹⁹F NMR resonance at δ –89.95, –90.33, and –93.20, respectively. They show satellite signals due to the coupling to the silicon atom with I_{Si-F} of 440, 442, and 428 Hz (Table 3). The ^{29}Si NMR spectra of **4–6** exhibit a doublet centered at δ 73.98 $(J_{\text{Si-F}} = 440 \text{ Hz})$, 56.65 $(J_{\text{Si-F}} = 442 \text{ Hz})$, and 41.79 $(J_{\text{Si-F}} = 428 \text{ Hz})$ Hz) each, which is shifted upfield compared to those of the silicon(II) chlorides 1–3. It is interesting to set side by side the above NMR data with those of $LSiF_3^{19d}$ {¹⁹F NMR, δ –132.38 $(J_{\text{Si}-\text{F}} = 219 \text{ Hz})$; ²⁹Si NMR, $\delta - 124.91$ $(J_{\text{Si}-\text{F}} = 219 \text{ Hz})$. In LSiF₃ both the ¹⁹F and ²⁹Si NMR resonances are shifted to higher field as expected when compared with those of 4-6. The reason might be due to the higher coordinate silicon in LSiF₃ which is unmatched to those of 4-6. The EI-MS spectra of compounds 4-6 exhibit their molecular ions at m/z 470, 516, and 602, respectively. In 4-6 the silicon atom is tetracoordinate with a distorted tetrahedral geometry comprising two nitrogen atoms from the amidinate ligand, one fluorine atom, and one metal atom. The metal atom each in 4, 5, and 6 features distorted octahedral geometry derived from one silicon atom and five carbon atoms of the carbonyl groups.



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Table 3. NMR and EI-MS Data for Compounds 4-6

compound	²⁹ Si (δ /ppm), J _{Si-F} /Hz	¹⁹ F (δ / ppm), $J_{\rm Si-F}$ / Hz	[M ⁺]/ amu
4	73.98, 440	-89.95, 440	470
5	56.65, 442	-90.33, 442	516
6	41.79, 428	-93.20, 428	602

The molecular structure of 4 is shown in Figure 2 (for 6, see Supporting Information), and the selected bond parameters for



Figure 2. Molecular structure of 4. Hydrogen atoms are omitted for clarity. Anisotropic displacement parameters are depicted at the 50% probability level.

compounds 4 and 6 are given in Table 2. There is a small variation in the Si-M bond distances in 4 and 6 after the replacement of the chlorine by the fluorine atom. The average metal carbonyl bond lengths in 4 and 6 are 1.8893(14) and 2.039(2) Å, respectively. These values are quite comparable to the chloro analogues of 1 and 3. The Si-F bond lengths in 4 and 6 are 1.6168(8) and 1.6245(14) Å and are close to those found in LSiF₃.^{19d} The bite angle (N–Si–N) for 4 and 6 is $71.62(5)^{\circ}$ and $70.93(8)^{\circ}$. A comparison of gaseous SiF₂ with its

Metal ion M	Ph-Cl			$\begin{array}{c c} & & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ & & \\ &$		
	SiCl / Å	Si-M / Å	N–Si–N / °	Si-F / Å	Si-M / Å	N-Si-N / °
Cr	2.1006(9)	2.3458(7)	71.62(8)	1.6168(8)	2.3398(4)	71.62(5)
Мо	2.1182(19)	2.4550(14)	71.34(18)			
W	2.1012(14)	2.5086(11)	71.41(12)	1.6245(14)	2.4990(8)	70.93(8)

Si–F bond length of 1.59 Å²⁰ indicates an increase in the bond length of only 0.03 Å. In contrast to that are the physical properties. SiF₂ is a gas at 25 °C and has a half-life of 150 s at <1 mmHg,^{10a} whereas the complexes **4–6** can be stored at room temperature in an inert atmosphere for a long period of time without decomposition.

CONCLUSION

Four and a half decades ago, Margrave, Timms, and co-workers generated the silicon(II) fluoride in the gas phase at high temperatures (~1100–1200 °C) and low pressures. They published their results in this journal. However, SiF₂ is unstable and readily disproportionates or polymerizes. Herein, we report on the first structurally characterized stable silicon(II) fluoride compounds that have been accomplished by utilizing the coordination sphere of transition metals. The compound L(F)Si·M(CO)₅ {M = Cr (4), Mo (5), W(6)} (L = PhC(NtBu)₂) contains the fluorosilylene moiety LSiF which coordinates to a transition metal carbonyl M(CO)₅ fragment. These compounds were prepared for the first time by metathesis reaction from the corresponding chloride with Me₃SnF. This approach marked a route to an easy access of low valent silicon fluorides.

EXPERIMENTAL SECTION

Syntheses were carried out under an inert gas atmosphere of dinitrogen in oven-dried glassware using standard Schlenk techniques, and other manipulations were accomplished in a dinitrogen filled glovebox. Solvents were purified by MBRAUN solvent purification system MB SPS-800. All chemicals were purchased from Aldrich and used without further purification. L(Cl)Si was prepared as reported in the literature.^{6e,f} ¹H, ¹³C, ¹⁹F, and ²⁹Si NMR spectra were recorded with a Bruker Avance DPX 300, or a Bruker Avance DRX 500 spectrometer, using C₆D₆ as solvent. Chemical shifts δ are given relative to SiMe₄. EI-MS spectra were obtained using a Finnigan MAT 8230 instrument. Elemental analyses were performed by the Institut für Anorganische Chemie, Universität Göttingen. Melting points were measured in sealed glass capillaries on a Büchi B-540 melting point apparatus.

General Procedure for the Synthesis of $LSi(CI) \cdot M(CO)_5$ {M = Cr (1), Mo (2), W(3)}. The respective $M(CO)_5(THF)$ complex was prepared by UV irradiation of the corresponding $M(CO)_6$ in THF as described in the literature.²¹ The prepared $M(CO)_5(THF)$ solution was added to the flask containing L(CI)Si. The mixture was stirred for 14 h at room temperature. Finally the solvent was removed *in vacuo* and extracted with toluene to obtain the corresponding $L(CI)Si \cdot M(CO)_5$.

Compound **1**. Quantity used: $Cr(CO)_{6^{\circ}}$ 1.00 g (4.54 mmol), L(Cl)Si, 1.34 g (4.54 mmol); yield (2.02 g, 91.4%). Mp 147–150 °C (d). Elemental analysis (%) calcd for $C_{20}H_{23}ClCrN_2O_3Si$ (486.94): C, 49.33; H, 4.76; N, 5.75. Found: C, 49.22; H, 4.62; N, 5.78. ¹H NMR (500 MHz, C_6D_6 , 25 °C): δ 1.09 (s, 18H, $C(CH_3)_3$), 6.79–6.93 (m, SH, C_6H_5) ppm. ¹³C{¹H} NMR (125.75 MHz, C_6D_6 , 25 °C): δ 30.52 C(CH₃)₃, 55.15 (C(CH₃)₃), 127.91, 128.19, 128.29, 128.35, 129.68, 130.77 (C_6H_5), 174.22 (NCN), 217.61 (CO), 219.76 (CO), 222.95 (CO) ppm. ²⁹Si{¹H} NMR (99.36 MHz, C_6D_6 , 25 °C): δ 92.34 ppm. EI-MS: *m/z*: 486 [M⁺], 458 [M⁺ – CO], 430 [M⁺ – 2CO], 402 [M⁺ – 3CO], 374 [M⁺ – 4CO], 346 [M⁺ – 5CO].

Compound **2**. Quantity used: Mo(CO)₆, 1.00 g (3.79 mmol), L(Cl)Si, 1.12 (3.80 mmol); yield (1.70 g, 84.2%). Mp 140–143 °C (d). Elemental analysis (%) calcd for C₂₀H₂₃ClMoN₂O₅Si (530.89): C, 45.25; H, 4.37; N, 5.28. Found: C, 45.16; H, 4.32; N, 5.12. ¹H NMR (500 MHz, C₆D₆, 25 °C): δ 1.09 (s, 18H, C(CH₃)₃), 6.79–6.94 (m, 5H, C₆H₅) ppm. ¹³C{¹H} NMR (125.75 MHz, C₆D₆, 25 °C): δ 30.72 C(CH₃)₃, 54.94 (C(CH₃)₃), 127.91, 128.25, 128.40, 128.56, 130.16, 130.77 (C₆H₅), 173.48 (NCN), 208.65 (CO), 210.50 (CO) ppm. ²⁹Si{¹H} NMR (99.36 MHz, C₆D₆, 25 °C): δ 72.75 ppm. EI-MS: *m/z*: 532 [M⁺], 504 [M⁺ – CO], 476 [M⁺ – 2CO], 448 [M⁺ – 3CO], 420 [M⁺ – 4CO], 392 [M⁺ – 5CO]. *Compound* **3**. Quantity used: W(CO)₆, 1.00 g (2.84 mmol), L(Cl)Si, 0.84 g (2.85 mmol); yield (1.50 g, 85.2%). Mp 142–145 °C (d). Elemental analysis (%) calcd for $C_{20}H_{23}ClN_2O_5SiW$ (618.79): C, 38.82; H, 3.75; N, 4.53. Found: C, 38.72; H, 3.72; N, 4.51. ¹H NMR (500 MHz, C_6D_6 , 25 °C): δ 1.09 (s, 18H, C(CH₃)₃), 6.81–6.93 (m, SH, C_6H_5) ppm. ¹³C{¹H} NMR (125.75 MHz, C_6D_6 , 25 °C): δ 30.71 C(CH₃)₃, 54.98 (C(CH₃)₃), 128.29, 128.40, 128.47, 129.53, 130.05, 130.88 (C_6H_5), 174.47 (NCN), 199.06 (CO), 200.07 (CO) ppm. ²⁹Si{¹H} NMR (99.36 MHz, C_6D_6 , 25 °C): δ 52.99 ppm. EI-MS: *m/z*: 618 [M⁺], 590 [M⁺ – CO], 562 [M⁺ – 2CO], 534 [M⁺ – 3CO], 506 [M⁺ – 4CO], 478 [M⁺ – 5CO].

General Procedure for the Synthesis of $L(F)Si \cdot M(CO)_5$ {M = Cr (4), Mo (5), W(6)}. THF (60 mL) was added to a 100 mL Schlenk flask containing corresponding $L(CI)Si \cdot M(CO)_5$ and Me₃SnF. The reaction mixture was stirred at room temperature for 36 h. After the completion of reaction, the solvent was removed *in vacuo* and the remaining substrate extracted with toluene (60 mL) to yield $L(F)Si \cdot M(CO)_5$.

Compound 4. Quantity used: L(Cl)Si-Cr(CO)₅, 0.30 g (0.62 mmol), Me₃SnF, 0.12 g (0.66 mmol); yield (0.24 g, 82.7%). Mp 107–110 °C (d). Elemental analysis (%) calcd for C₂₀H₂₃FCrN₂O₅Si (470.49): C, 51.06; H, 4.93; N, 5.95. Found: C, 50.96; H, 4.88; N, 5.86. ¹H NMR (300 MHz, C₆D₆, 25 °C): δ 1.05 (s, 18H, C(CH₃)₃), 6.82–6.91 (m, 5H, C₆H₅) ppm. ¹³C{¹H} NMR (125.75 MHz, C₆D₆, 25 °C): δ 30.91 C(CH₃)₃, 54.39 (C(CH₃)₃), 127.85, 128.20, 128.50, 128.62, 129.64, 130.75 (C₆H₅), 175.51 (NCN), 211.51 (CO), 220.34 (CO), 222.92 (CO) ppm. ²⁹Si{¹H} NMR (29.63 MHz, C₆D₆, 25 °C): δ 73.98 (d) ppm (J_{SiF} = 440 Hz). ¹⁹F{¹H} NMR (282.40 MHz, C₆D₆, 25 °C): δ ~89.95 ppm (J_{FSi} = 440 Hz). EI-MS: *m/z*: 470 [M⁺], 442 [M⁺ - CO], 414 [M⁺ - 2CO], 386 [M⁺ - 3CO], 358 [M⁺ - 4CO], 330 [M⁺ - 5CO].

Compound 5. Quantity used: L(Cl)Si·Mo(CO)₅, 0.35 g (0.66 mmol), Me₃SnF, 0.12 g (0. 66 mmol); yield (0.26 g, 76.5%). Mp 100–103 °C (d). Elemental analysis (%) calcd for C₂₀H₂₃FMoN₂O₅Si (S14.43): C, 46.70; H, 4.51; N, 5.45. Found: C, 46.66; H, 4.42; N, 5.38. ¹H NMR (300 MHz, C₆D₆, 25 °C): δ 1.06 (s, 18H, C(CH₃)₃), 6.80–6.93 (m, 5H, C₆H₅) ppm. ¹³C{¹H} NMR (125.75 MHz, C₆D₆, 25 °C): δ 30.87 C(CH₃)₃, 54.16 (C(CH₃)₃), 127.90, 128.20, 128.53, 128.70, 130.22, 130.65 (C₆H₅), 174.59 (NCN), 208.66 (CO), 209.13 (CO) ppm. ²⁹Si{¹H} NMR (99.36 MHz, C₆D₆, 25 °C): δ 56.65 (d) ppm (J_{SiF} = 442 Hz). ¹⁹F{¹H} NMR (282.40 MHz, C₆D₆, 25 °C): δ -90.33 ppm (J_{FSi} = 442 Hz). EI-MS: *m/z*: 516 [M⁺], 488 [M⁺ - CO], 460 [M⁺ - 2CO], 432 [M⁺ - 3CO], 404 [M⁺ - 4CO], 376 [M⁺ - 5CO].

Compound **6**. Quantity used: L(Cl)Si·W(CO)₅, 0.49 g (0.79 mmol), Me₃SnF, 0.15 g (0.82 mmol); yield (0.42 g, 87.5%). Mp 110–113 °C (d). Elemental analysis (%) calcd for C₂₀H₂₃FN₂O₅SiW (602.33): C, 39.88; H, 3.85; N, 4.65. Found: C, 39.83; H, 3.81; N, 4.62. ¹H NMR (500 MHz, C₆D₆, 25 °C): δ 1.07 (s, 18H, C(CH₃)₃), 6.80–6.91 (m, 5H, C₆H₅) ppm. ¹³C{¹H} NMR (125.75 MHz, C₆D₆, 25 °C): δ 30.86 C(CH₃)₃, 54.19 (C(CH₃)₃), 127.81, 128.30, 128.62, 128.64, 130.17, 130.75 (C₆H₅), 175.53 (NCN), 199.18 (CO), 200.48 (CO) ppm. ²⁹Si{¹H} NMR (59.63 MHz, C₆D₆, 25 °C): δ 41.79 (d) ppm (J_{SiF} = 428 Hz). ¹⁹F{¹H} NMR (282.40 MHz, C₆D₆, 25 °C): δ -93.20 ppm (J_{FSi} = 428 Hz). EI-MS: *m/z*: 602 [M⁺], 574 [M⁺ - CO], 546 [M⁺ - 3CO], 490 [M⁺ - 4CO], 462 [M⁺ - 5CO].

Crystal Structure Determination. Suitable single crystals for X-ray structural analysis of 1–4 and 6 were obtained by slow evaporation of their corresponding toluene solutions, and the crystals were mounted at low temperature in inert oil under argon atmosphere by applying the X-Temp2 device.²² The diffraction data were collected at 100 K on a Bruker D8 three circle diffractometer equipped with a SMART APEX II CCD detector and an INCOATEC Ag microsource with INCOATEC Quazar mirror optics ($\lambda = 0.5608$ Å). The data were integrated with SAINT,²³ and an empirical absorption correction with SADABS²⁴ was applied. The structures were solved by direct methods (SHELXS-97) and refined against all data by full-matrix least-squares methods on F^2 (SHELXL-97).²⁵ All non-hydrogen atoms were refined with anisotropic displacement parameters. The hydrogen atoms were refined with their U_{iso} values constrained to $1.5U_{eq}$ of their pivot atoms for terminal sp³ carbon atoms and 1.2 times for all other carbon atoms.

ASSOCIATED CONTENT

S Supporting Information

Molecular structures of **2**, **3**, and **6**. CIF files for **1**, **2**, **3**, **4**, and **6**. This material is available free of charge via the Internet at http://pubs.acs.org.

AUTHOR INFORMATION

Corresponding Author

hroesky@gwdg.de, rghadwal@uni-goettingen.de; dstalke@ chemie.uni-goettingen.de

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